

NS6130-10-1551

GADOLINIUM OXIDE Sputtering Target

Quick Facts

Product	:	Gadolinium Oxide Sputtering Target
Stock No	:	NS6130-10-1551
CAS	:	12064-62-9
Molecular Formula	:	Gd ₂ O ₃
Form	:	Solid

Technical Specification

Diameter	Thickness	Purity
50.8mm	3mm	99.99%

Gadolinium Oxide sputtering targets have a wide range of applications in the semiconductor industry, magnetic materials, high-k dielectric materials, catalysts, and phosphors. Gadolinium oxide sputtering targets are used to produce thin films of magneto-optic materials that can be used in data storage devices. Gadolinium oxide sputtering targets are used to deposit thin films of magnetic materials used in magnetic data storage, sensors, and other magnetic devices. Gadolinium oxide sputtering targets are used to produce high-k dielectric materials used in advanced semiconductor devices, such as DRAM (Dynamic Random Access Memory), which require high capacitance and low leakage current.



* This image is for graphic purposes only and does not represent the actual product.



ISO 9001:2015
CERTIFIED COMPANY

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